

There is an n-type of silicon which contains a concentration of donors: 10^{15} cm^{-3} . The n-type of silicon and aluminum were brought together and alloyed at $600 \text{ }^\circ\text{C}$. At the alloying temperature, a p/n junction was formed with an acceptor concentration which equals a solid solubility at the alloying temperature of $600 \text{ }^\circ\text{C}$.

- 1) Calculate the Fermi level positions ($E_{ip}-E_{FP}$) at 328K in the p region. (1 point)
 E_{ip} : Intrinsic fermi level on the p-side, E_{FP} : Fermi level on the p-side of a p/n junction.
- 2) Calculate the Fermi level positions ($E_{Fn}-E_{in}$) at 328K in the n region. (1 point)
 E_{Fn} : Fermi level on the n-side of a p/n junction, E_{in} : Intrinsic fermi level on the n-side
- 3) Calculate the contact potential V_{bi} (voltage drop across the depletion region under equilibrium conditions). (0.5 points)
- 4) Draw an equilibrium band diagram for the junction and put the numbers of $E_{ip}-E_{FP}$, $E_{Fn}-E_{in}$, and qV_{bi} in the diagram. (0.5 points)
- 5) Calculate the depletion region (W) under equilibrium conditions. Assume a Si step junction operated at 328K. (1 point)

Physical constants
 Boltzmann constant $8.62 \times 10^{-5} \text{ eV/K}$
 Permittivity of free space = $8.85 \times 10^{-14} \text{ farad/cm}$
 Si dielectric constant = 11.8
 Electronic charge = $1.60 \times 10^{-19} \text{ coul}$

